

WHEN MeV IONS MEET MATTER

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ION BEAM CHARACTERIZATION



Ion beams in the MeV energy range are versatile tool for both materials analysis and structuring. Violent interaction between MeV heavy ion and target material leads to diverse physical processes, which can be exploited in a number of ways. By adjusting ion beam parameters, interactions at the surface or deep in the bulk can be chosen. Additional opportunities offer an ion microbeam setup, where low beam current or even single ion irradiations are possible. In this contribution, few recent examples of both materials analysis and modifications by MeV heavy ion beams are presented.



Ion implantation: a) Injection of foreign atoms

Single ion tracks: Fast and heavy ions (~MeV/amu) create latent tracks of damage used as a template in nanostructuring

b) Displacement of atoms

Irradiation with protons: Produce homogeneous radiation damage that car be used for lithography, defect engineering, etc...



Creating nanometar sized tracks

STIM (Scanning Transmission Ion Microscopy)

polycarbonate Whatman etched ion track membrane was scanned with focused He microbeam. Position and energy of transmitted ions were used for 3D profiling (unpublished).



PIXE (Particle induced X-ray Emission)

Proton microbeam was scanned over the lateral cross-section of a painting to investigate elemental composition of used pigments. Energy and intensity of x-rays emitted from the sample for each position of scanning beam measured. Obtained were maps show elemental distribution throughout the crosssection.







Laboratory for ion beam interactions at RBI is equipped with two accelerators: 6.0 MV Tandem Van De Graaff and 1.0 MV HVE Tandetron and several beam lines dedicated to ion beam applications. Dual beam chamber makes possible in-situ RBS/c analysis during MeV heavy ion irradiation or implantation. Ion microprobe with new quintuplet focusing system is able to focus heavy ions down to 300 nm expanding also opportunities for modification of materials.

with MeV heavy ions

Random tracks

created with broad beam of 35 MeV Cl ions in PMMA



(a)







References [1] M. Buljan et al, Appl. Phys. Lett. 95 (2009) 063104

Miniature wavelength

dispersive X ray spectrometer

Use of small beam size with ion microprobe and CCD detector as a position sensitive detector, miniature WDX spectrometer was constructed for measuring influence of chemical effects on x-ray spectra and to resolve lines that can not be separated with energy dispersive systems.





(Ge+SiO₂) / SiO₂ multilayer irradiated with 3 MeV ${}^{16}O^{3+}$ under angle of 60°, dose 10¹⁵ ion/cm²[1], [2]

Creation of ordered nanodots in SrTiO₃ by swift heavy ions

Recent discovery of chainlike-nanodot morphology of surface ion tracks in SrTiO₃ [3] generated strong scientific interest in detailed investigations of ion tracks. At RBI, original experiment was successfully repeated at lower energies and threshold for ion track formation was found [4]. We have also investigated ion tracks in the bulk SrTiO₃ using RBS/c at HZDR, Dresden, Germany within EU FP7 SPIRIT project. Much higher threshold was established and a novelty - its angular dependence was found. Extension of themal spike model was developed at RBI which explains observed features (unpublished). Recently, in-situ RBS/c setup is constructed and tested at RBI.







